Masaharu Shiratani

List of Publications by Year
in descending order

336	5,522	94433	138484
papers	citations	37 h-index	58 g-index

342	342	342	3135
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Morphological control of nanostructured Ge films in high Ar-gas-pressure plasma sputtering process for Li ion batteries. Japanese Journal of Applied Physics, 2022, 61, SA1002.	1.5	4
2	Improved luminescence performance of Yb3+-Er3+-Zn2+: Y2O3 phosphor and its application to solar cells. Optical Materials, 2022, 123, 111928.	3.6	4
3	Effect of gas flow rate and discharge volume on CO₂ methanation with plasma catalysis. Japanese Journal of Applied Physics, 2022, 61, SI1002.	1.5	7
4	Nanostructured Ge and GeSn films by high-pressure He plasma sputtering for high-capacity Li ion battery anodes. Scientific Reports, 2022, 12, 1742.	3.3	9
5	Outcomes of Pulsed Electric Fields and Nonthermal Plasma Treatments on Seed Germination and Protein Functions. Agronomy, 2022, 12, 482.	3.0	12
6	Growth of Single-Crystalline ZnO Films on 18%-Lattice-Mismatched Sapphire Substrates Using Buffer Layers with Three-Dimensional Islands. Crystal Growth and Design, 2022, 22, 3770-3777.	3.0	4
7	Effects of amplitude modulated capacitively coupled discharge Ar plasma on kinetic energy and angular distribution function of ions impinging on electrodes: particle-in-cell/Monte Carlo collision model simulation. Japanese Journal of Applied Physics, 2022, 61, 106003.	1.5	2
8	Mechanistic Insight into Permeation of Plasma-Generated Species from Vacuum into Water Bulk. International Journal of Molecular Sciences, 2022, 23, 6330.	4.1	5
9	Treatment of organic wastewater by a combination of non-thermal plasma and catalyst: a review. Reviews of Modern Plasma Physics, 2022, 6, .	4.1	11
10	Synthesis of Yb3+/Ho3+ co-doped Y2O3 nanoparticles and its application to dye sensitized solar cells. Journal of Molecular Structure, 2021, 1228, 129479.	3.6	12
11	Longâ€term response of Norway spruce to seed treatment with cold plasma: Dependence of the effects on the genotype. Plasma Processes and Polymers, 2021, 18, 2000159.	3.0	11
12	Impact of seed color and storage time on the radish seed germination and sprout growth in plasma agriculture. Scientific Reports, 2021, 11, 2539.	3.3	28
13	Possible impact of plasma oxidation on the structure of the C-terminal domain of SARS-CoV-2 spike protein: a computational study. Applied Physics Express, 2021, 14, 027002.	2.4	13
14	Green route for ammonium nitrate synthesis: fertilizer for plant growth enhancement. RSC Advances, 2021, 11, 28521-28529.	3.6	9
15	Alterations of DNA Methylation Caused by Cold Plasma Treatment Restore Delayed Germination of Heat-Stressed Rice (Oryza sativa L.) Seeds. ACS Agricultural Science and Technology, 2021, 1, 5-10.	2.3	32
16	Impact of atmospheric pressure plasma treated seeds on germination, morphology, gene expression and biochemical responses. Japanese Journal of Applied Physics, 2021, 60, 040502.	1.5	24
17	Sputtering Growth of Metal Oxynitride Semiconductors for Excitonic Devices. , 2021, , .		0
18	Highly efficient and transparent counter electrode for application in bifacial solar cells. Chemical Physics Letters, 2021, 768, 138369.	2.6	6

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19	Comparison between Ar+CH4 cathode and anode coupling chemical vapor depositions of hydrogenated amorphous carbon films. Thin Solid Films, 2021, 729, 138701.	1.8	5
20	Plasma treatment causes structural modifications in lysozyme, and increases cytotoxicity towards cancer cells. International Journal of Biological Macromolecules, 2021, 182, 1724-1736.	7.5	21
21	Impact of Reactive Oxygen and Nitrogen Species Produced by Plasma on Mdm2â€“p53 Complex. International Journal of Molecular Sciences, 2021, 22, 9585.	4.1	5
22	Passivating antireflection coating of crystalline silicon using i/n a-Si:H/SiN trilayer. Journal of Physics and Chemistry of Solids, 2021, 156, 110127.	4.0	9
23	Effects of concentrated light on the performance and stability of a quasi-solid electrolyte in dye-sensitized solar cells. Chemical Physics Letters, 2021, 781, 138986.	2.6	5
24	Time of Flight Size Control of Carbon Nanoparticles Using Ar+CH4 Multi-Hollow Discharge Plasma Chemical Vapor Deposition Method. Processes, 2021, 9, 2.	2.8	5
25	Impact of surface morphologies of substrates on the epitaxial growth of magnetron-sputtered (ZnO) _x (InN)_{1-x} films. Japanese Journal of Applied Physics, 2021, 60, SAAB02.	1.5	3
26	Effect of hydrogen dilution on the silicon cluster volume fraction of a hydrogenated amorphous silicon film prepared using plasma-enhanced chemical vapor deposition. Current Applied Physics, 2020, 20, 191-195.	2.4	2
27	Relationship between cold plasma treatment-induced changes in radish seed germination and phytohormone balance. Japanese Journal of Applied Physics, 2020, 59, SH1001.	1.5	30
28	Real-time monitoring of surface passivation of crystalline silicon during growth of amorphous and epitaxial silicon layer. Journal of Applied Physics, 2020, 128, 033302.	2.5	8
29	Size and flux of carbon nanoparticles synthesized by Ar+CH4 multi-hollow plasma chemical vapor deposition. Diamond and Related Materials, 2020, 109, 108050.	3.9	14
30	Graphene-Si3N4 nanocomposite blended polymer counter electrode for low-cost dye-sensitized solar cells. Chemical Physics Letters, 2020, 758, 137920.	2.6	7
31	Plasma Agriculture from Laboratory to Farm: A Review. Processes, 2020, 8, 1002.	2.8	125
32	Cold Plasma Treatment of Sunflower Seeds Modulates Plant-Associated Microbiome and Stimulates Root and Lateral Organ Growth. Frontiers in Plant Science, 2020, 11, 568924.	3.6	20
33	Cold plasma treatment of Arabidopsis thaliana (L.) seeds modulates plant-associated microbiome composition. Applied Physics Express, 2020, 13, 076001.	2.4	13
34	Growth of single crystalline films on lattice-mismatched substrates through 3D to 2D mode transition. Scientific Reports, 2020, 10, 4669.	3.3	21
35	Characteristics of crystalline sputtered LaFeO₃ thin films as photoelectrochemical water splitting photocathodes. Nanoscale, 2020, 12, 9653-9660.	5.6	23
36	Improved Nanoscale Al-Doped ZnO with a ZnO Buffer Layer Fabricated by Nitrogen-Mediated Crystallization for Flexible Optoelectronic Devices. ACS Applied Nano Materials, 2020, 3, 2480-2490.	5.0	10

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37	Impact of radish sprouts seeds coat color on the electron paramagnetic resonance signals after plasma treatment. Japanese Journal of Applied Physics, 2020, 59, SHHF01.	1.5	20
38	Influence of osmolytes and ionic liquids on the Bacteriorhodopsin structure in the absence and presence of oxidative stress: A combined experimental and computational study. International Journal of Biological Macromolecules, 2020, 148, 657-665.	7.5	13
39	Effects of surrounding gas on plasma-induced downward liquid flow. Japanese Journal of Applied Physics, 2020, 59, SHHF02.	1.5	7
40	Influence of alkyl chain substitution of ammonium ionic liquids on the activity and stability of tobacco etch virus protease. International Journal of Biological Macromolecules, 2020, 155, 439-446.	7.5	8
41	Structural modification of NADPH oxidase activator (Noxa 1) by oxidative stress: An experimental and computational study. International Journal of Biological Macromolecules, 2020, 163, 2405-2414.	7.5	19
42	Plasma Treatment Effect on the Paramagnetic Species of Barley Seed Radical's Intensity: An EPR Study. Plasma Medicine, 2020, 10, 159-168.	0.6	4
43	Low-stress diamond-like carbon films containing carbon nanoparticles fabricated by combining rf sputtering and plasma chemical vapor deposition. Japanese Journal of Applied Physics, 2020, 59, 100906.	1.5	3
44	Experimental identification of the reactive oxygen species transported into a liquid by plasma irradiation. Japanese Journal of Applied Physics, 2020, 59, 110502.	1.5	8
45	Impact of heterointerface properties of crystalline germanium heterojunction solar cells. Thin Solid Films, 2019, 685, 225-233.	1.8	4
46	Effects of nitrogen impurity on zno crystal growth on Si substrates. MRS Advances, 2019, 4, 1557-1563.	0.9	0
47	Identification and Suppression of Si-H₂Bond Formation at P/I Interface in a-Si:H Films Deposited by SiH₄Plasma CVD. Plasma and Fusion Research, 2019, 14, 4406141-4406141.	0.7	1
48	Effects of Gas Pressure on the Size Distribution and Structure of Carbon Nanoparticles Using Ar + CH₄Multi-Hollow Discharged Plasma Chemical Vapor Deposition. Plasma and Fusion Research, 2019, 14, 4406115-4406115.	0.7	4
49	Dielectric barrier discharge plasma treatment-induced changes in sunflower seed germination, phytohormone balance, and seedling growth. Applied Physics Express, 2019, 12, 126003.	2.4	28
50	Local supply of reactive oxygen species into a tissue model by atmospheric-pressure plasma-jet exposure. Journal of Applied Physics, 2019, 125, 213303.	2.5	17
51	Sputter Epitaxy of (ZnO)x(InN)1-x films on Lattice-mismatched Sapphire Substrate. MRS Advances, 2019, 4, 1551-1556.	0.9	3
52	Visualization Study on Interaction Between Nonequilibrium Atmospheric Pressure He Plasma Jet and Liquid Solution. Journal of Smart Processing, 2019, 8, 58-63.	0.1	0
53	Spatial-Structure of Fluctuation of Amount of Nanoparticles in Amplitude-Modulated VHF Discharge Reactive Plasma. Plasma and Fusion Research, 2019, 14, 4406120-4406120.	0.7	2
54	Effect of Higher-Order Silane Deposition on Spatial Profile of Si-H₂/Si-H Bond Density Ratio of a-Si:H Films. Plasma and Fusion Research, 2019, 14, 4406144-4406144.	0.7	0

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55	The effect of the H2/(H2â€¯+â€¯Ar) flow-rate ratio on hydrogenated amorphous carbon films grown using Ar/H2/C7H8 plasma chemical vapor deposition. Thin Solid Films, 2018, 660, 891-898.	1.8	4
56	Impact of Gamma rays and DBD plasma treatments on wastewater treatment. Scientific Reports, 2018, 8, 2926.	3.3	49
57	Progress in photovoltaic performance of organic/inorganic hybrid solar cell based on optimal resistive Si and solvent modified poly(3,4â€ethylenedioxythiophene) poly(styrenesulfonate) junction. Progress in Photovoltaics: Research and Applications, 2018, 26, 145-150.	8.1	11
58	Current status and future prospects of agricultural applications using atmosphericâ€pressure plasma technologies. Plasma Processes and Polymers, 2018, 15, 1700073.	3.0	156
59	Transportation of reactive oxygen species in a tissue phantom after plasma irradiation. Japanese Journal of Applied Physics, 2018, 57, 01AG01.	1.5	6
60	Plasma agriculture: A rapidly emerging field. Plasma Processes and Polymers, 2018, 15, 1700174.	3.0	174
61	Effects of Sputtering Pressure on (ZnO)_x(InN)_{1-x} Crystal Film Growth at 450Â°C. Materials Science Forum, 2018, 941, 2093-2098.	0.3	0
62	Cross-Correlation Analysis of Fluctuations of Interactions between Nanoparticles and Low Pressure Reactive Plasmas. Materials Science Forum, 2018, 941, 2104-2108.	0.3	0
63	Morphology Evolution Of ZnO Thin Films Deposited By Nitrogen Mediated Crystallization Method. MATEC Web of Conferences, 2018, 159, 02031.	0.2	3
64	Particle behavior and its contribution to film growth in a remote silane plasma. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, 050601.	2.1	1
65	Dependence of CO₂ Conversion to CH₄on the CO₂ Flow Rate in a Helicon Discharge Plasma. Science of Advanced Materials, 2018, 10, 655-659.	0.7	4
66	Low-Pressure Methanation of CO₂ Using a Plasmaâ€“Catalyst System. Science of Advanced Materials, 2018, 10, 1087-1090.	0.7	5
67	Effects of Gas Velocity on Deposition Rate and Amount of Cluster Incorporation into a-Si:H Films Fabricated by SiH₄Plasma Chemical Vapor Deposition. Plasma and Fusion Research, 2018, 13, 1406082-1406082.	0.7	5
68	Hysteresis in volume fraction of clusters incorporated into a-Si:H films deposited by SiH 4 plasma chemical vapor deposition. Surface and Coatings Technology, 2017, 326, 388-394.	4.8	6
69	Densities and Surface Reaction Probabilities of Oxygen and Nitrogen Atoms During Sputter Deposition of ZnInON on ZnO. IEEE Transactions on Plasma Science, 2017, 45, 323-327.	1.3	11
70	Enhanced light harvesting and charge recombination control with TiO2/PbCdS/CdS based quantum dot-sensitized solar cells. Journal of Electroanalytical Chemistry, 2017, 788, 131-136.	3.8	24
71	Plant Growth Enhancement of Seeds Immersed in Plasma Activated Water. MRS Advances, 2017, 2, 995-1000.	0.9	38
72	Synthesis of Nanoparticles Using Low Temperature Plasmas and Its Application to Solar Cells and Tracers in Living Body. ECS Transactions, 2017, 77, 17-24.	0.5	0

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73	Low temperature rapid formation of Au-induced crystalline Ge films using sputtering deposition. Thin Solid Films, 2017, 641, 59-64.	1.8	5
74	Effects of sputtering gas pressure dependence of surface morphology of ZnO films fabricated via nitrogen mediated crystallization. MRS Advances, 2017, 2, 265-270.	0.9	4
75	Blue Photoluminescence of (ZnO)0.92(InN)0.08. MRS Advances, 2017, 2, 277-282.	0.9	8
76	The protective action of osmolytes on the deleterious effects of gamma rays and atmospheric pressure plasma on protein conformational changes. Scientific Reports, 2017, 7, 8698.	3.3	19
77	Impact of an ionic liquid on protein thermodynamics in the presence of cold atmospheric plasma and gamma rays. Physical Chemistry Chemical Physics, 2017, 19, 25277-25288.	2.8	19
78	Performance enhancement of quantum dot-sensitized solar cells based on polymer nano-composite catalyst. Electrochimica Acta, 2017, 249, 337-342.	5.2	2
79	Biogenic reductive preparation of magnetic inverse spinel iron oxide nanoparticles for the adsorption removal of heavy metals. Chemical Engineering Journal, 2017, 307, 74-84.	12.7	226
80	Response of Silkworm Larvae to Atmospheric Pressure Nonthermal Plasma Irradiation. Plasma Medicine, 2016, 6, 349-359.	0.6	1
81	DNA Microarray Analysis of Plant Seeds Irradiated by Active Oxygen Species in Oxygen Plasma. Plasma Medicine, 2016, 6, 459-471.	0.6	15
82	Effect of sulfur doped TiO2 on photovoltaic properties of dye-sensitized solar cells. Electronic Materials Letters, 2016, 12, 530-536.	2.2	13
83	Inter-particle potential fluctuation of two fine particles suspended in Ar plasmas. , 2016, , .		0
84	Correlation between SiH₂/SiH and light-induced degradation of pâ€“iâ€“n hydrogenated amorphous silicon solar cells. Japanese Journal of Applied Physics, 2016, 55, 07LE03.	1.5	8
85	Effects of nonthermal plasma jet irradiation on the selective production of H2O2 and NO2â^' in liquid water. Journal of Applied Physics, 2016, 120, .	2.5	52
86	Fluctuation of Position and Energy of a Fine Particle in Plasma Nanofabrication. Materials Science Forum, 2016, 879, 1772-1777.	0.3	5
87	Two-dimensional concentration distribution of reactive oxygen species transported through a tissue phantom by atmospheric-pressure plasma-jet irradiation. Applied Physics Express, 2016, 9, 076202.	2.4	41
88	Effects of irradiation distance on supply of reactive oxygen species to the bottom of a Petri dish filled with liquid by an atmospheric O2/He plasma jet. Journal of Applied Physics, 2016, 119, .	2.5	36
89	Low temperature synthesis of silicon quantum dots with plasma chemistry control in dual frequency non-thermal plasmas. Physical Chemistry Chemical Physics, 2016, 18, 15697-15710.	2.8	16
90	Room Temperature Fabrication of (ZnO)x(InN)1-x films with Step-Terrace Structure by RF Magnetron Sputtering. MRS Advances, 2016, 1, 115-119.	0.9	9

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91	Improving the performance of quantum dot sensitized solar cells through CdNiS quantum dots with reduced recombination and enhanced electron lifetime. Dalton Transactions, 2016, 45, 8447-8457.	3.3	44
92	Optical Bandgap Energy of Si Nanoparticle Composite Films Deposited by a Multi-Hollow Discharge Plasma Chemical Vapor Deposition Method. Journal of Nanoscience and Nanotechnology, 2016, 16, 10753-10757.	0.9	2
93	Variation in structure of proteins by adjusting reactive oxygen and nitrogen species generated from dielectric barrier discharge jet. Scientific Reports, 2016, 6, 35883.	3.3	40
94	Mechanism and comparison of needle-type non-thermal direct and indirect atmospheric pressure plasma jets on the degradation of dyes. Scientific Reports, 2016, 6, 34419.	3.3	71
95	Production of In, Au, and Pt nanoparticles by discharge plasmas in water for assessment of their bio-compatibility and toxicity. MRS Advances, 2016, 1, 1301-1306.	0.9	0
96	Relationship between electric properties and surface flatness of (ZnO)<inf>x</inf>(InN)<inf>1âˆ'x</inf> films on ZnO templates. , 2016, , .		0
97	Plant Growth Response to Atmospheric Air Plasma Treatments of Seeds of 5 Plant Species. MRS Advances, 2016, 1, 1265-1269.	0.9	9
98	Surface Modification of Polymer Counter Electrode for Low Cost Dye-sensitized Solar Cells. Electrochimica Acta, 2016, 210, 880-887.	5.2	12
99	Catalytic Improvement on Counter Electrode of Dye-Sensitized Solar Cells Using Electrospun Pt Nano-Fibers. Journal of Nanoscience and Nanotechnology, 2016, 16, 3332-3337.	0.9	1
100	Effects of plasma irradiation using various feeding gases on growth of Raphanus sativus L.. Archives of Biochemistry and Biophysics, 2016, 605, 129-140.	3.0	64
101	Improvement of Charge Transportation in Si Quantum Dot-Sensitized Solar Cells Using Vanadium Doped TiO₂. Journal of Nanoscience and Nanotechnology, 2016, 16, 4875-4879.	0.9	4
102	Effects of gas flow rate on deposition rate and number of Si clusters incorporated into a-Si:H films. Japanese Journal of Applied Physics, 2016, 55, 01AA19.	1.5	5
103	Reduced recombination with an optimized barrier layer on TiO₂ in PbS/CdS core shell quantum dot sensitized solar cells. New Journal of Chemistry, 2016, 40, 3423-3431.	2.8	23
104	Simple method of improving harvest by nonthermal air plasma irradiation of seeds of Arabidopsis thaliana (L.). Applied Physics Express, 2016, 9, 016201.	2.4	83
105	Polymer counter electrode of poly(3,4-ethylenedioxythiophene):Poly(4-styrenesulfonate) containing TiO2 nano-particles for dye-sensitized solar cells. Journal of Power Sources, 2016, 307, 25-30.	7.8	32
106	Quantum Characterization of Si Nano-Particles Fabricated by Multi-Hollow Discharge Plasma Chemical Vapor Deposition. Science of Advanced Materials, 2016, 8, 636-639.	0.7	1
107	Effects of deposition rate and ion bombardment on properties of a-C:H films deposited by H-assisted plasma CVD method. Japanese Journal of Applied Physics, 2016, 55, 01AA11.	1.5	9
108	Fabrication of p-i-n solar cells utilizing ZnInON by RF magnetron sputtering. Materials Research Society Symposia Proceedings, 2015, 1741, 53.	0.1	3

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109	Antioxidative activity and growth regulation of Brassicaceae induced by oxygen radical irradiation. Japanese Journal of Applied Physics, 2015, 54, 06GD01.	1.5	40
110	Effects of gas flow on oxidation reaction in liquid induced by He/O2 plasma-jet irradiation. Journal of Applied Physics, 2015, 118, .	2.5	39
111	Influence of ionic liquid and ionic salt on protein against the reactive species generated using dielectric barrier discharge plasma. Scientific Reports, 2015, 5, 17781.	3.3	70
112	Deposition of Germanium Crystalline Nanoparticle Composite Films by Using Reactive Dusty Plasma Process and their Application for Quantum-Dot Solar Cells. Journal of Smart Processing, 2015, 4, 6-11.	0.1	0
113	Effects of Atmospheric Air Plasma Irradiation to Seeds of Radish Sprouts on Chlorophyll and Carotenoids Concentrations in their Leaves. Materials Research Society Symposia Proceedings, 2015, 1723, 34.	0.1	4
114	Effects of morphology of buffer layers on ZnO/sapphire heteroepitaxial growth by RF magnetron sputtering. Materials Research Society Symposia Proceedings, 2015, 1741, 33.	0.1	4
115	Comparative Study on the Pulmonary Toxicity of Indium Hydroxide, Indium-Tin Oxide, and Indium Oxide Following Intratracheal Instillations into the Lungs of Rats. Materials Research Society Symposia Proceedings, 2015, 1723, 19.	0.1	0
116	Fabrication of ZnInON/ZnO multi-quantum well solar cells. Thin Solid Films, 2015, 587, 106-111.	1.8	15
117	Real-time mass measurement of dust particles deposited on vessel wall in a divertor simulator using quartz crystal microbalances. Journal of Nuclear Materials, 2015, 463, 865-868.	2.7	2
118	Synthesis of Indium-Containing Nanoparticles in Aqueous Suspension Using Plasmas in Water for Evaluating Their Kinetics in Living Body. Journal of Nanoscience and Nanotechnology, 2015, 15, 9298-9302.	0.9	1
119	Effects of cluster incorporation into hydrogenated amorphous silicon films in initial discharge phase on film stability. Thin Solid Films, 2015, 587, 126-131.	1.8	10
120	Multigeneration Effects of Plasma Irradiation to Seeds of Arabidopsis Thaliana and Zinnia on Their Growth. Materials Research Society Symposia Proceedings, 2015, 1723, 7.	0.1	7
121	Photovoltaic application of Si nanoparticles fabricated by multihollow plasma discharge CVD: Dye and Si co-sensitized solar cells. Japanese Journal of Applied Physics, 2015, 54, 01AD02.	1.5	4
122	Structural alternation of tandem dye-sensitized solar cells based on mesh-type of counter electrode. Electrochimica Acta, 2015, 179, 206-210.	5.2	4
123	Gas Flow Rate Dependence of the Discharge Characteristics of a Plasma Jet Impinging Onto the Liquid Surface. IEEE Transactions on Plasma Science, 2015, 43, 4081-4087.	1.3	13
124	Deposition of Carbon Films on PMMA Using H-assisted Plasma CVD. , 2014, , .		0
125	Growth mechanism of ZnO deposited by nitrogen mediated crystallization. Materials Research Express, 2014, 1, 036403.	1.6	6
126	Self-organized formation of hierarchically-ordered structures in laser-activated plasma CVD of sp3-bonded BN films. Japanese Journal of Applied Physics, 2014, 53, 010202.	1.5	1

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127	Formation of microcones accompanied with ripple patterns in laser-activated plasma CVD of sp³-bonded BN films. Journal of Materials Research, 2014, 29, 485-491.	2.6	0
128	Sterilization characteristics of the surfaces of agricultural products using active oxygen species generated by atmospheric plasma and UV light. Japanese Journal of Applied Physics, 2014, 53, 05FR03.	1.5	30
129	Off-axis sputter deposition of ZnO films on c-sapphire substrates by utilizing nitrogen-mediated crystallization method. Optical Engineering, 2014, 53, 087109.	1.0	10
130	Study on the Crystal Growth Mechanism of ZnO Films Fabricated Via Nitrogen Mediated Crystallization.. , 2014, , .		0
131	Performance dependence of Si quantum dot-sensitized solar cells on counter electrode. Japanese Journal of Applied Physics, 2014, 53, 05FZ01.	1.5	4
132	SiC Nanoparticle Composite Anode for Li-Ion Batteries. Materials Research Society Symposia Proceedings, 2014, 1678, 7.	0.1	7
133	Electrochemical impedance analysis on the additional layers for the enhancement on the performance of dye-sensitized solar cell. Thin Solid Films, 2014, 554, 122-126.	1.8	7
134	Plasma induced long-term growth enhancement of Raphanus sativus L. using combinatorial atmospheric air dielectric barrier discharge plasmas. Current Applied Physics, 2014, 14, S149-S153.	2.4	85
135	Analysis on the photovoltaic property of Si quantum dot-sensitized solar cells. International Journal of Precision Engineering and Manufacturing, 2014, 15, 339-343.	2.2	5
136	Effects of Atmospheric Air Plasma Irradiation on pH of Water. , 2014, , .		3
137	Dust Hour Glass in a Capacitive RF Discharge. IEEE Transactions on Plasma Science, 2014, 42, 2672-2673.	1.3	2
138	Visualization of the Distribution of Oxidizing Substances in an Atmospheric Pressure Plasma Jet. IEEE Transactions on Plasma Science, 2014, 42, 2482-2483.	1.3	30
139	Theory for correlation between plasma fluctuation and fluctuation of nanoparticle growth in reactive plasmas. Japanese Journal of Applied Physics, 2014, 53, 010201.	1.5	9
140	The enhancement of dye adsorption in dye-sensitized solar module by an electrical adsorption method. Thin Solid Films, 2014, 554, 118-121.	1.8	7
141	Effects of Grid DC Bias on Incorporation of Si Clusters into Amorphous Silicon Thin Films in Multi-Hollow Discharge Plasma CVD. , 2014, , .		0
142	Performance enhancement of dye and Si quantum dot hybrid nanostructured solar cell with TiO₂ barrier. Transactions of the Materials Research Society of Japan, 2014, 39, 321-324.	0.2	0
143	Effects of H2 Gas Addition on Structure of Ge Nanoparticle Films Deposited by High-Pressure RF Magnetron Sputtering Method. , 2014, , .		0
144	Combinatorial Plasma CVD of Si Nanoparticle Composite Films for Band Gap Control. , 2014, , .		0

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145	Mass density control of carbon films deposited by H-assisted plasma CVD method. Surface and Coatings Technology, 2013, 228, S15-S18.	4.8	9
146	Transport control of dust particles via the electrical asymmetry effect: experiment, simulation and modelling. Journal Physics D: Applied Physics, 2013, 46, 245202.	2.8	16
147	Growth control of ZnO nano-rod with various seeds and photovoltaic application. Journal of Physics: Conference Series, 2013, 441, 012029.	0.4	1
148	Analysis on the effect of polysulfide electrolyte composition for higher performance of Si quantum dot-sensitized solar cells. Electrochimica Acta, 2013, 95, 43-47.	5.2	31
149	Characteristics of photocurrent generation in the near-ultraviolet region in Si quantum-dot sensitized solar cells. Thin Solid Films, 2013, 544, 93-98.	1.8	10
150	The improvement on the performance of quantum dot-sensitized solar cells with functionalized Si. Thin Solid Films, 2013, 546, 284-288.	1.8	6
151	Effects of nanoparticle incorporation on properties of microcrystalline films deposited using multi-hollow discharge plasma CVD. Surface and Coatings Technology, 2013, 228, S550-S553.	4.8	1
152	Discharge power dependence of carbon dust flux in a divertor simulator. Journal of Nuclear Materials, 2013, 438, S788-S791.	2.7	5
153	The reduction of charge recombination and performance enhancement by the surface modification of Si quantum dot-sensitized solar cell. Electrochimica Acta, 2013, 87, 213-217.	5.2	18
154	Effects of DC substrate bias voltage on dust flux in the Large Helical Device. Journal of Nuclear Materials, 2013, 438, S727-S730.	2.7	5
155	Dust particle formation due to interaction between graphite and helicon deuterium plasmas. Fusion Engineering and Design, 2013, 88, 28-32.	1.9	10
156	Plasma interactions with aminoacid (l-alanine) as a basis of fundamental processes in plasma medicine. Current Applied Physics, 2013, 13, S59-S63.	2.4	22
157	High Amount Cluster Incorporation in Initial Si Film Deposition by SiH4Plasma Chemical Vapor Deposition. Japanese Journal of Applied Physics, 2013, 52, 01AD01.	1.5	12
158	H2/N2Plasma Etching Rate of Carbon Films Deposited by H-Assisted Plasma Chemical Vapor Deposition. Japanese Journal of Applied Physics, 2013, 52, 01AB01.	1.5	3
159	Correlation between Volume Fraction of Silicon Clusters in Amorphous Silicon Films and Optical Emission Properties of Si[*]and SiH[*]. Japanese Journal of Applied Physics, 2013, 52, 11NA07.	1.5	4
160	Improvement of Si Adhesion and Reduction of Electron Recombination for Si Quantum Dot-Sensitized Solar Cells. Japanese Journal of Applied Physics, 2013, 52, 01AD05.	1.5	12
161	Flux Control of Carbon Nanoparticles Generated due to Interactions between Hydrogen Plasmas and Graphite Using DC-Biased Substrates. Japanese Journal of Applied Physics, 2013, 52, 11NA08.	1.5	2
162	Characteristics of Crystalline Silicon/Si Quantum Dot/Poly(3,4-ethylenedioxythiophene) Hybrid Solar Cells. Japanese Journal of Applied Physics, 2013, 52, 11NA05.	1.5	1

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163	Effects of Nitrogen on Crystal Growth of Sputter-Deposited ZnO Films for Transparent Conducting Oxide. Japanese Journal of Applied Physics, 2013, 52, 11NB03.	1.5	14
164	Improvement on the Electron Transfer of Dye-Sensitized Solar Cell Using Vanadium Doped TiO₂. Japanese Journal of Applied Physics, 2013, 52, 11NM02.	1.5	11
165	Epitaxial Growth of ZnInON Films with Tunable Band Gap from 1.7 to 3.3 eV on ZnO Templates. Japanese Journal of Applied Physics, 2013, 52, 11NM06.	1.5	16
166	Study on the Fabrication of Paint-Type Si Quantum Dot-Sensitized Solar Cells. Japanese Journal of Applied Physics, 2013, 52, 10MB07.	1.5	7
167	Effects of Hydrogen Dilution on ZnO Thin Films Fabricated via Nitrogen-Mediated Crystallization. Japanese Journal of Applied Physics, 2013, 52, 01AC08.	1.5	9
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